L Number	Hits	Search Text	DB ·	Time stamp
1	2	jp-2000035665-\$.did.	USPAT;	2003/07/09 08:57
1 -]p-2000033003-3.414.	US-PGPUB;	2003,01,03 00.31
			EPO; JPO;	
ľ			DERWENT	
1 -	2	(("20020068237") or ("20020068236")).PN.	US-PGPUB	2003/07/09 08:57
_	1975440		USPAT;	2003/07/07 12:06
	13/3110	Testi resise photoresise	US-PGPUB;	2003,01,07
			EPO; JPO;	
			DERWENT	
_	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 12:06
		(F	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	78586	photosensitizer sensitizer	USPAT;	2003/07/07 12:05
1			US-PGPUB;	
		5 cot sealch	EPO; JPO;	
1		East search	DERWENT	
-	1008314	solvent	USPAT;	2003/07/03 13:46
			US-PGPUB;	
			EPO; JPO;	
1			DERWENT	_ , _ ,
-	1234	(resin resist photoresist) and ((photoacid	USPAT;	2003/07/03 13:49
	1	acid) near generat\$3) and (photosensitizer	US-PGPUB;	
	1	sensitizer) and solvent	EPO; JPO;	
1		1,	DERWENT	
1 -	5890	benzopyran	USPAT;	2003/07/07 12:06
l			US-PGPUB;	
			EPO; JPO;	
		(/	DERWENT	0000/05/05 44 40
-	25		USPAT;	2003/07/07 11:40
		acid) near generat\$3) and (photosensitizer	US-PGPUB;	
		sensitizer) and solvent) and benzopyran	EPO; JPO;	
	155	IMAL C IMAL CENTOUT IMAL CENTI	DERWENT	2002/07/08 16-22
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT;	2003/07/08 16:22
			US-PGPUB; EPO; JPO;	
			DERWENT	
_	6	(IMAI-G IMAI-GENICHI IMAI-GENJI)_and	USPAT;	2003/07/07 12:01
		benzopyran	US-PGPUB;	2003/07/07 12:01
		benzopyran	EPO; JPO;	
			DERWENT	
-	78586	photosensitizer sensitizer	USPAT;	2003/07/07 12:06
		DO NOT REMOVES	US-PGPUB;	
	\perp	(V) (V)	EPO; JPO;	
	K	DIVOJ KUIUVOS	DERWENT	
-	5890	benzopyran	USPAT;	2003/07/07 12:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	·
-	61	(photosensitizer sensitizer) same	USPAT;	2003/07/07 12:08
		benzopyran	US-PGPUB;	
			EPO; JPO;	
			DERWENT	0000 100 100 10
-	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 17:04
1			US-PGPUB;	
	1		EPO; JPO;	
	1975440	rogin rogist photograpist	DERWENT USPAT:	2003/07/07 12:06
1-	19/5440	resin resist photoresist	USPAT; US-PGPUB;	2003/07/07 12:06
1			EPO; JPO;	
	1		DERWENT	
-	7	((photosensitizer sensitizer) same	USPAT;	2003/07/07 12:07
	'	benzopyran) and ((photoacid acid) near	US-PGPUB;	2003,07,07 12.07
		generat\$3) and (resin resist photoresist)	EPO; JPO;	
		January , and (100111 100100 photo100100)	DERWENT	
_	3	(((photosensitizer sensitizer) same	USPAT;	2003/07/07 12:07
		benzopyran) and ((photoacid acid) near	US-PGPUB;	
		generat\$3) and (resin resist photoresist))	EPO; JPO;	
		not ((IMAI-G IMAI-GENICHI PMAI-GENJI) and	DERWENT	
		benzopyran)		

•				
-	20	((photosensitizer sensitizer) same	USPAT;	2003/07/07 12:08
	1	benzopyran) and (resin resist photoresist)	US-PGPUB;	
1	1		EPO; JPO;	
		///	DERWENT	2003/07/07 12:10
1 -	13		USPAT; US-PGPUB;	2003/07/07 12:10
	į.	benzopyran) and (resin resist photoresist)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI)	EPO; JPO;	
		and benzopyran) (((photosensitizer	DERWENT	
1	İ	sensitizer) same benzopyran) and	DERMENT	
1		((photoacid acid) near generat\$3) and		
		(resin resist photoresist)))]	i
-	0	jp-8334897-\$.did.	USPAT;	2003/07/07 12:10
	_	SF	US-PGPUB;	, ,
			EPO; JPO;	
			DERWENT	
-	2	jp-08334897-\$.did.	USPAT;	2003/07/07 12:26
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-11212252-\$.did. or jp-2000275823 or	USPAT;	2003/07/07 12:27
		jp-2000056450	US-PGPUB;	
			EPO; JPO;	
	_	/ 110100ED 6 444	DERWENT	2002/07/07 10 07
-	6	(jp-11212252-\$.did. or jp-2000275823 or	USPAT;	2003/07/07 12:27
		jp-2000056450) jp-09138502-\$.did.	US-PGPUB;	
		jp-2000035665-\$.did.	EPO; JPO; DERWENT	
_	2	jp-2000035665-\$.did.	USPAT;	2003/07/07 12:49
-] JP-2000033663-3.did.	US-PGPUB;	2003/07/07 12:43
			EPO; JPO;	
			DERWENT	
_	2	titanocene same (\$5acid near generator)	USPAT;	2003/07/07 13:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1	(titanocene adj compound) same (\$5acid near	USPAT;	2003/07/07 13:47
		generator)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	((titanocene adj compound) same (\$5acid near	USPAT;	2003/07/07 13:48
		generator)) not (titanocene same (\$5acid	US-PGPUB;	
		near generator))	EPO; JPO; DERWENT	
l _	51	(radical adj generator) same ((acid	USPAT;	2003/07/07 14:24
	7	photoacid) near generator)	US-PGPUB;	2003,07,07 11.21
			EPO; JPO;	
			DERWENT	
-	900	(resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)	EPO; JPO;	
			DERWENT	
-	509	((resin resist photoresist binder) and	USPAT;	2003/07/07 14:26
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative	EPO; JPO;	
	2707022	who ho countries a countries	DERWENT	2002/07/07 14 27
-	3797882	photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross	USPAT; US-PGPUB;	2003/07/07 14:27
		adj link\$4) cross-link\$4	EPO; JPO;	
		ddj IIInyt/ CIOSS-IIInyt	DERWENT	
-	509	(((resin resist photoresist binder) and	USPAT;	2003/07/07 14:28
		((photoacid acid) near generator) and	US-PGPUB;	,
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and (photocurable curable cur\$5 negative	DERWENT	
		crosslinkable crosslinked crosslink (cross		
		adj link\$4) cross-link\$4)		
-	4167371	dry drying heat-treat\$5 (heat\$5) bak\$4	USPAT;	2003/07/07 14:30
1		pre-bake\$4	US-PGPUB;	
			EPO; JPO;	
	I		DERWENT	

-	4553605	<pre>coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))</pre>	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:31
-	1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:31
-	1640490	develop development developing developed)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	360309	(visible adj light) "VIS"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	57817	(dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:33
	208	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed }) and ((visible adj light) "VIS"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:37
-	50	<pre>((((resin resist photoresist binder) and ((photoacid acid) near generator) and ((photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:41
-	27	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))) and (peel	USPAT; EPO; JPO; DERWENT	2003/07/07 15:48
-	2	peeling peelable peeled (peel\$4-apart) (peel\$4 near apart)) ("6033826").PN.	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 15:48
-	1	(("6033826").PN.) and (generator) and (\$5\$sensitizer)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 16:31

-	32	pyrene same (benzopyran)	USPAT; US-PGPUB;	2003/07/07 15:54
	1		EPO; JPO;	
			DERWENT	
j -	18	(((((resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative)	EPO; JPO; DERWENT	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying	DERWENT	
		applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
		irradiated irradiation) and (develop development developing developed]) and		
		((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart))) and ((visible VIS)		
1		near light)		
	0	((((((resin resist photoresist binder) and ((photoacid acid) near generator) and	USPAT; US-PGPUB;	2003/07/07 17:02
ļ	-	(photosensitizer sensitizer)) and negative)	EPO; JPO;	
	1	and ((dry drying heat-treat\$5 (heat\$5) bak\$4	DERWENT	
		pre-bake\$4) and (coat coating apply applying		
		applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed		
		irradiated irradiation) and (develop		
		development developing developed]) and		
		((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart) (peel\$4 near apart)		
		near light)) and benzopyran		
-	0	(((((resin resist photoresist binder) and	USPAT;	2003/07/07 17:02
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4	EPO; JPO; DERWENT	
		pre-bake\$4) and (coat coating apply applying	DERMENT	
		applied coated spin-coated spin-coat (spin		j
	:	adj (coated coat coating))) and (irradiate		
	•	irradiating expose exposure exposing exposed irradiated irradiation) and (develop		
		development developing developed]) and		
		((visible adj light) "VIS"))) and (peel		
ļ		peeling peelable peeled (peel\$4-apart)		
_	2248	(peel\$4 near apart))) and benzopyran	USPAT;	2003/07/07 17:02
_	2248	((visible adj light) "VIS") and benzopyran	US-PGPUB;	2003/07/07 17:02
			EPO; JPO;	
			DERWENT	0000 (00 (55 55 55
-	395		USPAT; US-PGPUB;	2003/07/07 17:03
	ļ	and ((visible VIS) near light)	EPO; JPO;	
	i		DERWENT	
-	293	(resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
	1	((((visible adj light) "VIS") and	US-PGPUB;	
		benzopyran) and ((visible VIS) near light))	EPO; JPO; DERWENT	
_	21	((photoacid acid) near generat\$3) and	USPAT;	2003/07/07 17:45
		((resin resist photoresist binder) and	US-PGPUB;	
		((((visible adj light) "VIS") and	EPO; JPO;	
		benzopyran) and ((visible VIS) near light)))	DERWENT	2002/02/02 10:04
-	1	ls-148	USPAT; US-PGPUB;	2003/07/07 18:04
			EPO; JPO;	
			DERWENT	
-	2	JP-11258798-\$.DID.	USPAT;	2003/07/07 18:04
			US-PGPUB; EPO; JPO;	
			DERWENT	
	L,		~~~~	

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-	2	benzopyran adj condensed adj ring	USPAT;	2003/07/08 11:34
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	7521	condensed adj ring	USPAT;	2003/07/08 11:53
ŀ			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	72	proliferating adj agent	USPAT;	2003/07/08 13:48
1			US-PGPUB;	
1			EPO; JPO;	
			DERWENT	2000/05/00 20 00
-	2661	sodium adj lamp	USPAT;	2003/07/08 12:09
			US-PGPUB;	
			EPO; JPO;	
	120	(andium adi lama) samo (nm wawlength)	DERWENT USPAT;	2003/07/08 12:10
-	120	(sodium adj lamp) same (nm wavlength)	US-PGPUB;	2003/07/08 12.10
			EPO; JPO;	
			DERWENT	
l _	72	proliferating adj agent	USPAT;	2003/07/08 14:31
	/2	profiferating adj agent	US-PGPUB;	2003/07/00 11.31
1			EPO; JPO;	
1		·	DERWENT	
l -	2	jp-09138502-\$.did.	USPAT;	2003/07/08 13:50
1		JE Timeson.	US-PGPUB;	
1			EPO; JPO;	
			DERWENT	1
-	2	("6140025").PN.	USPAT;	2003/07/08 14:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	į l
-	12	(proliferating adj agent) and (resin resist	USPAT;	2003/07/08 14:09
		photoresist)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	(proliferating adj agent) same ((fluidity	USPAT;	2003/07/08 14:35
		adj adjuster) (adhesion adj improver)	US-PGPUB;	
		(cissing adj inhibitor) (polymerization adj	EPO; JPO;	1
		inhibitor) pigment plasticizer)	DERWENT	0000/05/00 14 50
-	134	(organic adj acid adj ester) same ((fluidity	USPAT;	2003/07/08 14:58
		adj adjuster) (adhesion adj improver)	US-PGPUB;	!
,		(cissing adj inhibitor) (polymerization adj	EPO; JPO; DERWENT	
l _	83	inhibitor) pigment plasticizer) ((organic adj acid adj ester) same	USPAT;	2003/07/08 14:58
-	"	((fluidity adj adjuster) (adhesion adj	US-PGPUB;	2003/07/08 14:38
		improver) (cissing adj inhibitor)	EPO; JPO;	
		(polymerization adj inhibitor) pigment	DERWENT	
		plasticizer)) and (resist photoresist resin)		
_	79	((organic adj acid adj ester) same	USPAT;	2003/07/08 14:46
		((fluidity adj adjuster) (adhesion adj	EPO; JPO;	
		improver) (cissing adj inhibitor)	DERWENT	
		(polymerization adj inhibitor) pigment		
		plasticizer)) and (resist photoresist resin)		
-	2648	(organic adj acid adj ester)	USPAT;	2003/07/08 14:58
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1070	((organic adj acid adj ester)) and (resist	USPAT;	2003/07/08 14:59
· ·		photoresist resin)	US-PGPUB;	
			EPO; JPO;	
		(/	DERWENT	2002/07/02 25 25
-	834	((organic adj acid adj ester)) and (resist	USPAT	2003/07/08 15:13
		photoresist resin)	USPAT	2003/07/08 15:00
-	0 2718	430.270.1.ccls.	USPAT	
-	2718	430/270.1.ccls.	USPAT	2003/07/08 15:09 2003/07/08 15:01
1	5	430/270.1.ccls. and (((organic adj acid adj ester)) and (resist photoresist resin))	OSFAI	2003/01/00 15:01
1_	6	430/270.1.ccls. and ((organic adj acid adj	USPAT	2003/07/08 15:08
		ester))		13.00
1	1			,

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-	1	(430/270.1.ccls. and ((organic adj acid adj	USPAT	2003/07/08 1	15:08
	_	ester))) not (430/270.1.ccls. and	'	' '	
		(((organic adj acid adj ester)) and (resist			
		photoresist resin)))		i .	
_	112	430/\$.ccls. and ((organic adj acid adj	USPAT	2003/07/08 1	15:11
		ester))			
-	5270	430/\$.ccls. and (organic adj acid)	USPAT	2003/07/08 1	15:12
_		430/270.1.ccls. and (organic adj acid)	USPAT	2003/07/08 1	15:12
-	269		USPAT	2003/07/08 1	15:23
0		(resist photoresist resin)			
_	89		USPAT	2003/07/08 1	L5:30
		and (resist photoresist resin)) and (visible			
		near light)			
-	44		USPAT	2003/07/08 1	16:20
		and (resist photoresist resin)) and (visible			
		near light)) and negative			
-	97	positive and ((photoacid acid) near	USPAT	2003/07/08 1	L6:21
		generator) and (photosensitizer sensitizer)			
1		and (visible near light)		l	
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT;	2003/07/08 1	L6:22
			US-PGPUB;		
			EPO; JPO;		
			DERWENT	, _ , _ , ,	
-	2	(positive and ((photoacid acid) near	USPAT;	2003/07/08 1	16:33
		generator) and (photosensitizer sensitizer)	US-PGPUB;	1	
		and (visible near light)) and (IMAI-G	EPO; JPO;		
		IMAI-GENICHI IMAI-GENJI)	DERWENT	0000 (00 (00)	
-	2	("5801212").PN.	USPAT;	2003/07/08 1	16:33
			US-PGPUB;		
			EPO; JPO;		